

Paper #	First Name	Last Name	Company	Title	Duration	Start	Finish
All Times are local time in Austin, Texas, USA (US Central Time Zone)							
December 10, 2024, 8 AM - 11 AM, US Central Time - Please estimate your local time!							
<i>Version: December 3, 2024. For questions or comments please contact info@euvlitho.com</i>							
Paper #	First Name	Last Name	Company	Title / Topic	Duration	Start	Finish
Session 1 Chair: Mordy RorhsChild (MIT LL)							
1	Vivek	Bakshi	EUV Litho	Blue-X TWG: An Overview	0:12	8:00 AM	8:12 AM
2	Junji	Yumoto	The University of Tokyo	Pioneering the Future of EUVL: A New Initiative in Japan	0:12	8:12 AM	8:24 AM
Session 2: Chair: Oscar Versolato (ARCNL)							
3	Takeshi	Higashiguchi	Utsunomiya University	Short Wavelength Sources in the 6.7 nm and Water Window Region	0:12	8:24 AM	8:36 AM
4	David	Reisman	Energetiq	Next-generation Discharge-Produced Plasma SXR/Blue-X Source	0:12	8:36 AM	8:48 AM
5	Nicholas	Kelez	xLight	FEL Sources in the 6.7 nm and Water Window region	0:12	8:48 AM	9:00 AM
Session 3: Chair: Patrick Naulleau (EUV Tech)							
6	Sangsul	Lee	POSTECH	Infrastructure in the 6.7 nm and water window region at POSTECH	0:12	9:00 AM	9:12 AM
7	Bruno	LaFontaine	LBNL	ALS beamlines for experiments in the 6.7 nm and Water Window region (Tentative)	0:12	9:12 AM	9:24 AM
				Break	0:10	9:24 AM	9:34 AM
Session 4: Chair: Allen Gabor (IBM)							
8	Vladimir	Liberman	MIT LL	Beyond-EUV Thin Film Multilayer Coatings	0:12	9:34 AM	9:46 AM
9	Ladislav	Pina	Rigaku	GI optics for < 13.5 nm sources	0:12	9:46 AM	9:58 AM

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	10	Ibrahim	Burki	Hoya	Mask Blank Requirements and Challenges Beyond EUV	0:12	9:58 AM	10:10 AM
Session 5: Chair: Anuja Silva (LAM)								
	11	Mordy	Rothchild	MIT LL	Resists at Sub-13.5nm Wavelengths	0:12	10:10 AM	10:22 AM
	12	Michael	Tsapatsis	John Hopkins	Resists in the 6.7 nm and Water Window region (Tentative)	0:12	10:22 AM	10:34 AM
	13	Allen	Gabor	IBM	IBM Lithography Roadmap: Short wave-length options	0:12	10:34 AM	10:46 AM
	14	Patrick	Naulleau	EUV Tech	Metrology at sub 13.5 nm wavelengths	0:12	10:46 AM	10:58 AM
Meeting Adjourned								